

nano aperture ion source

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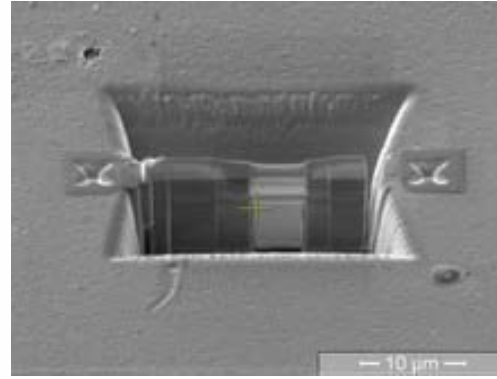
HR focused ion beams: applications



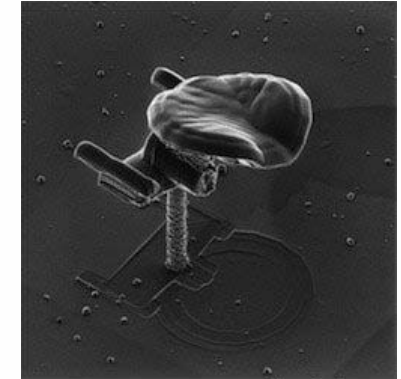
fabrication



cross sections



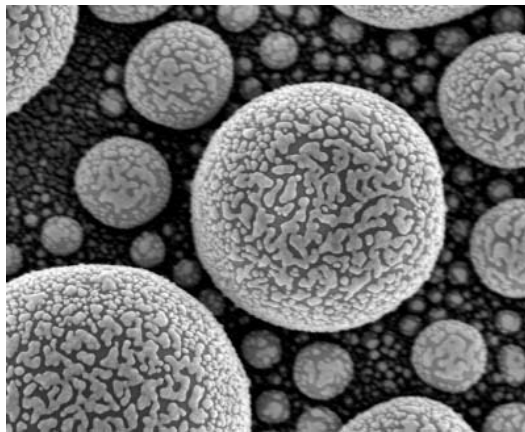
TEM lamella



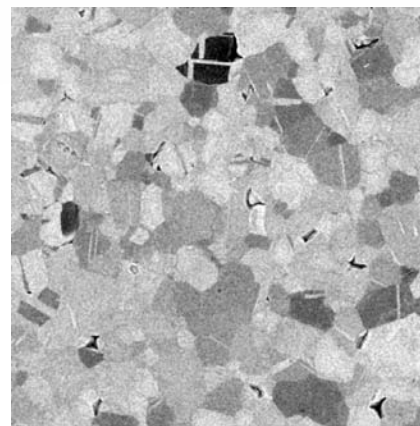
Zyvexlabs.com

...

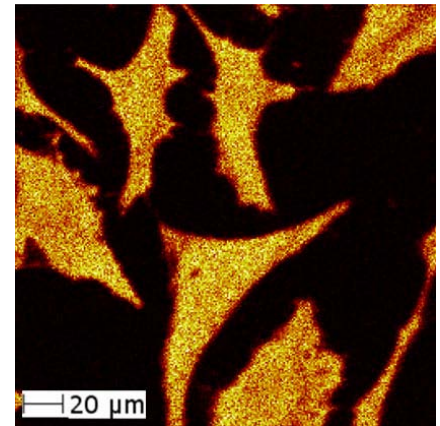
imaging



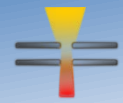
high surface contrast



channeling contrast



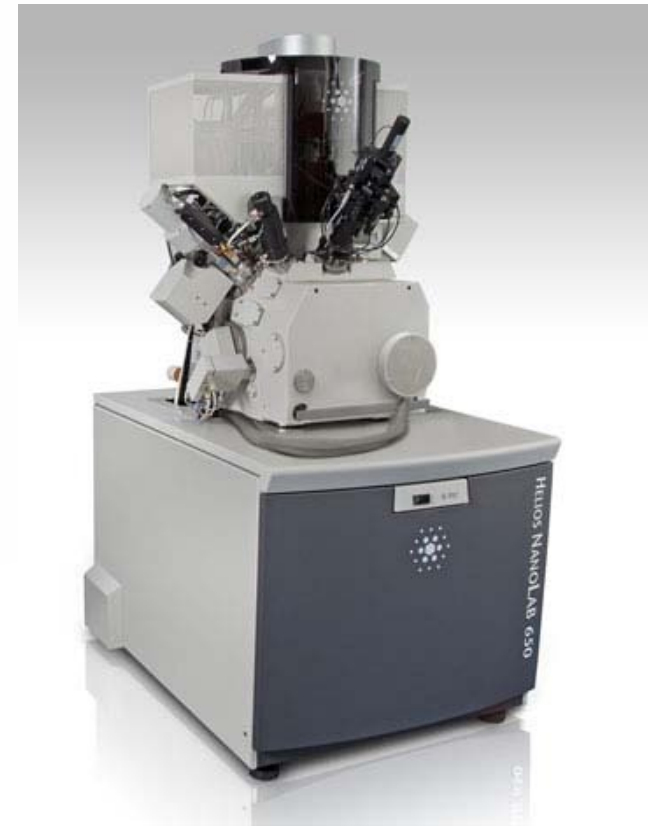
SIMS

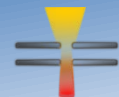


Helium ion microscope



LMIS (Galium)





Helium ion microscope



LMIS (Galium)



Various gas species enable

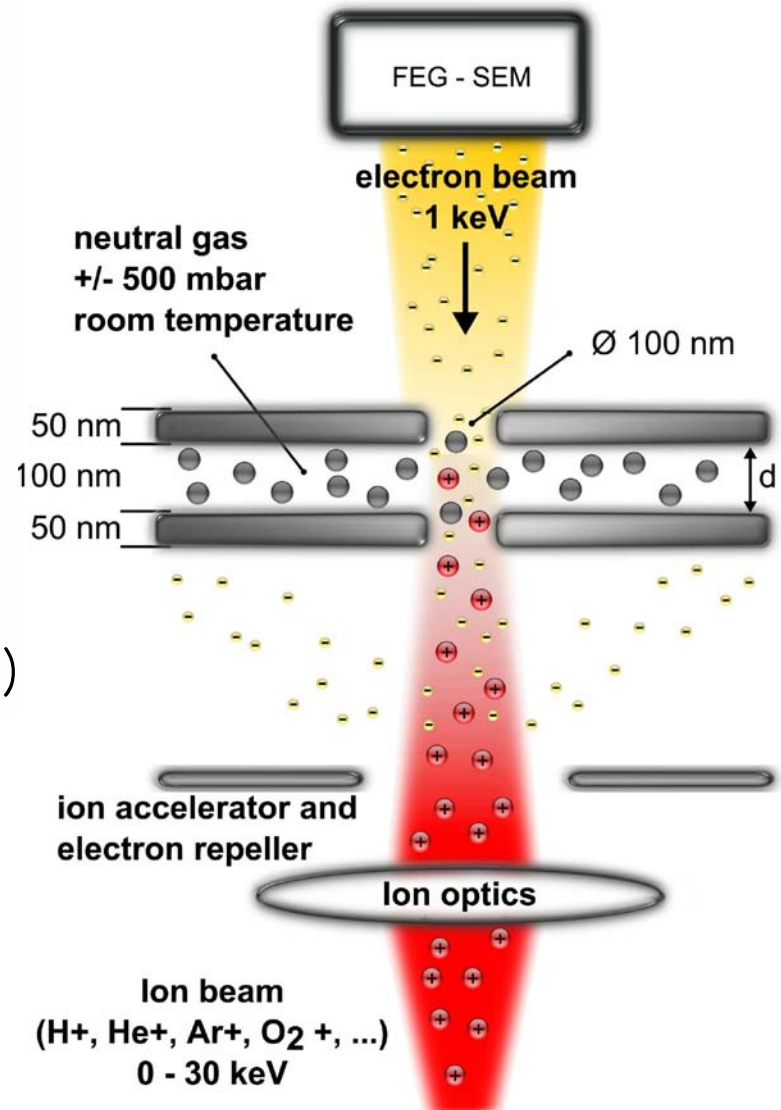
- no contamination in nano-structures
- efficient sputtering
- imaging with little sputtering
- Ion implantation

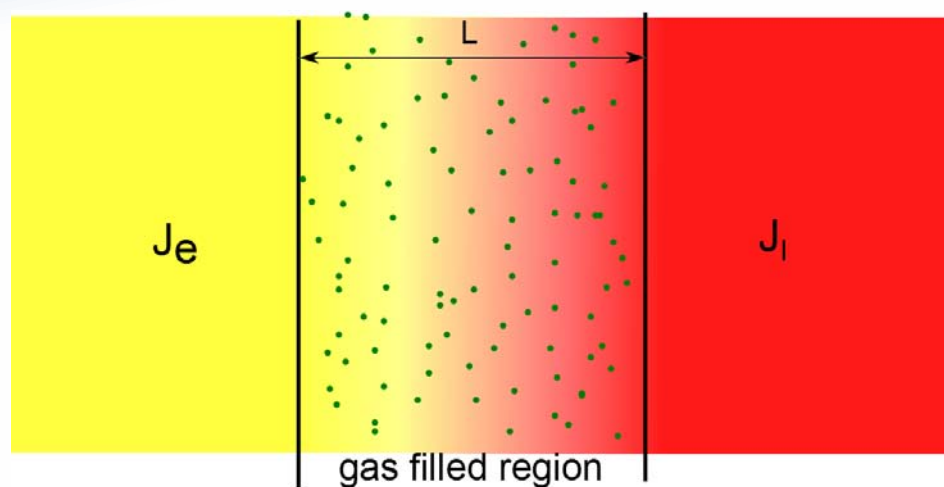
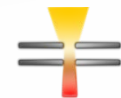


electron impact ionization
sub-micron gas chamber

- micromachined membranes
- high intensity e-beam (schottky)

any gas possible





reduced brightness

$$B_r = \frac{eJ}{\pi kT}$$

Ion current density

$$J = J_e (1 - e^{-\sigma_I n l}) \approx J_e \sigma_I n L$$

low ion-neutral interaction

$$L = \text{ion mean free path} = \frac{1}{n\sigma_C}$$

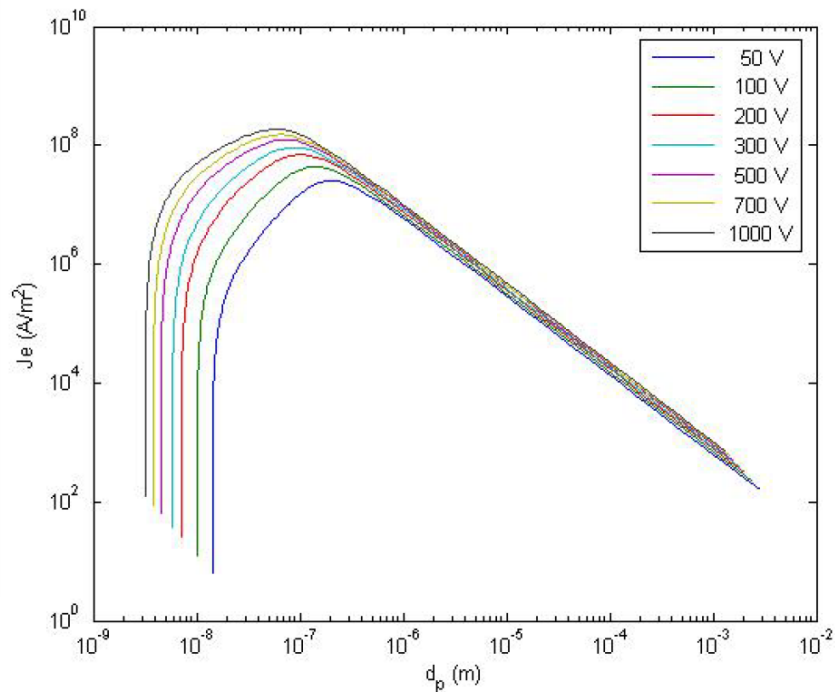
$$B_r = \frac{e \sigma_I J_e}{\pi \sigma_C kT}$$

max [(ionization cross section) x (electron current density)]

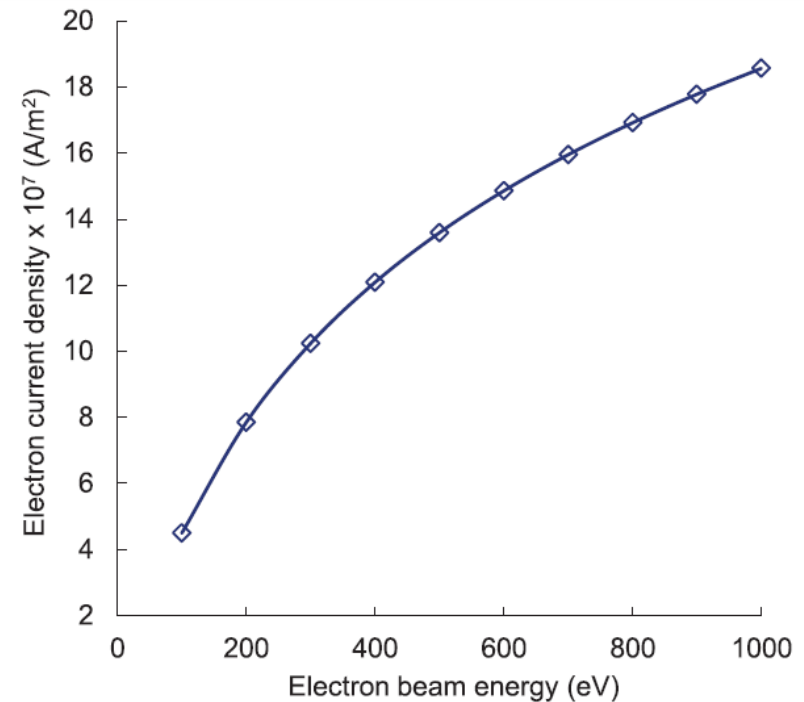


- Typical schottky and electron optical column specs:

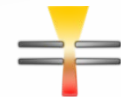
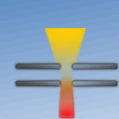
electron current density*



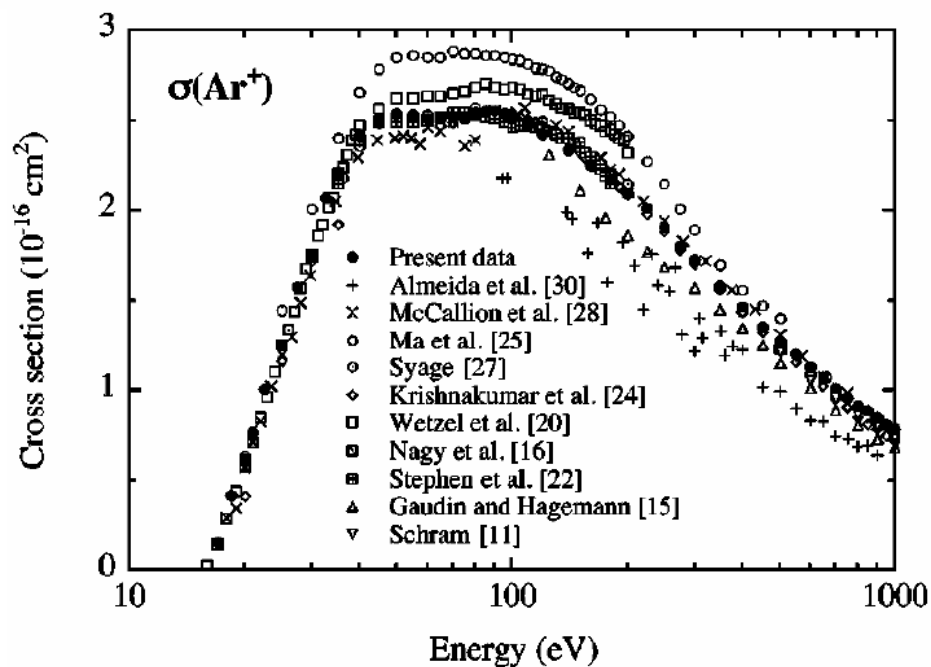
electron current density

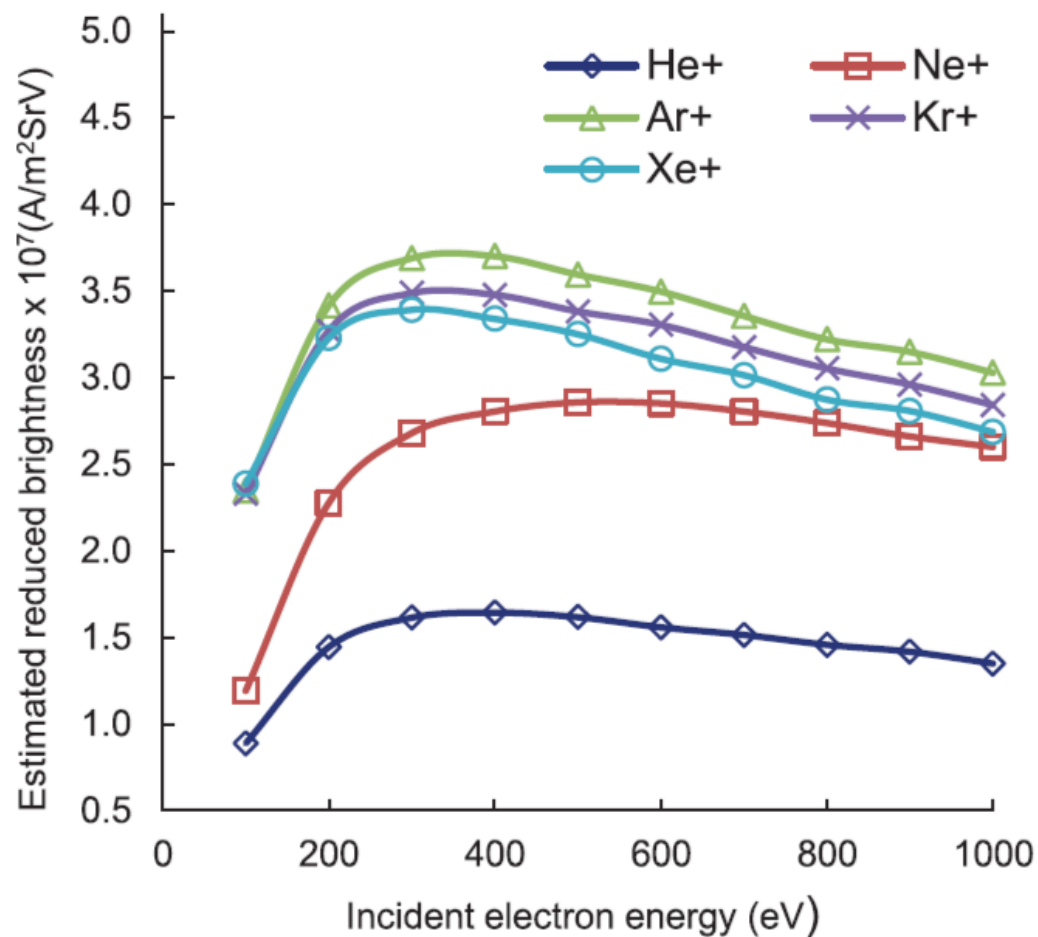


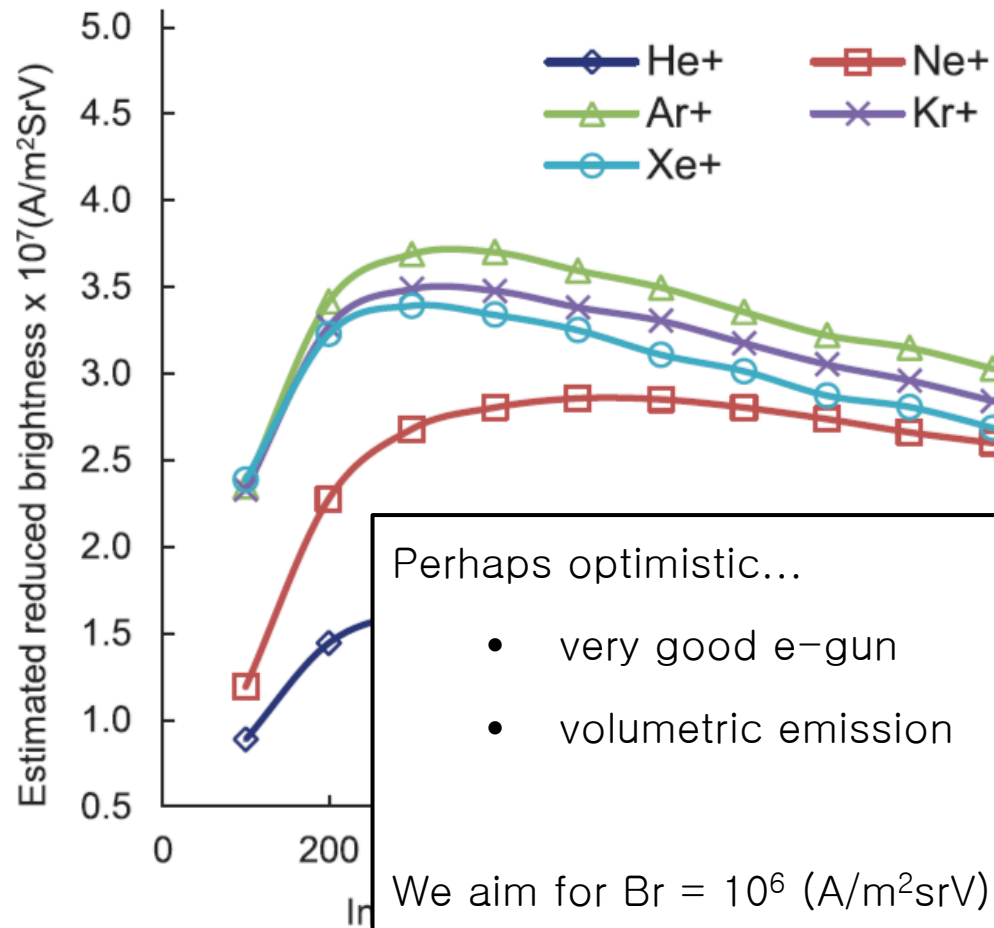
*V.N. Tondare



ionization cross section



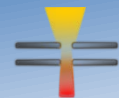




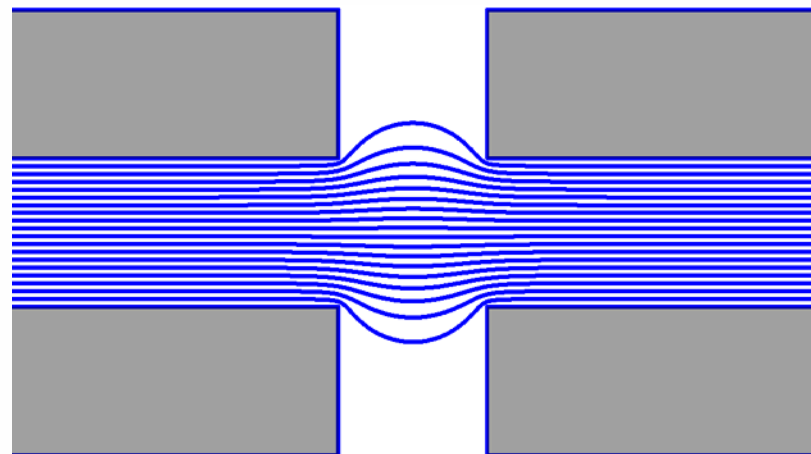
Perhaps optimistic...

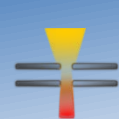
- very good e-gun
- volumetric emission

We aim for $\text{Br} = 10^6 \text{ (A/m}^2 \text{ srV)}$

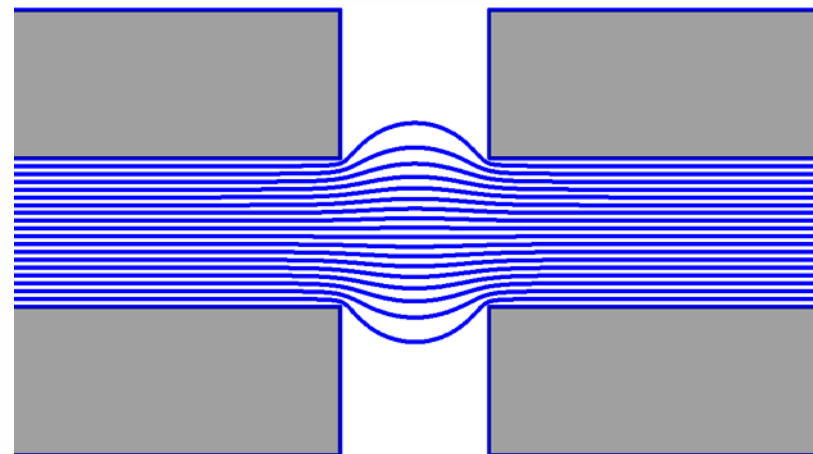


- Bias voltage
 - determines energy spread
 - prevents ion-ion interactions





- Bias voltage
 - determines energy spread
 - prevents ion-ion interactions



membrane spacing: 100nm
bias voltage: 0.3 V
Argon gas



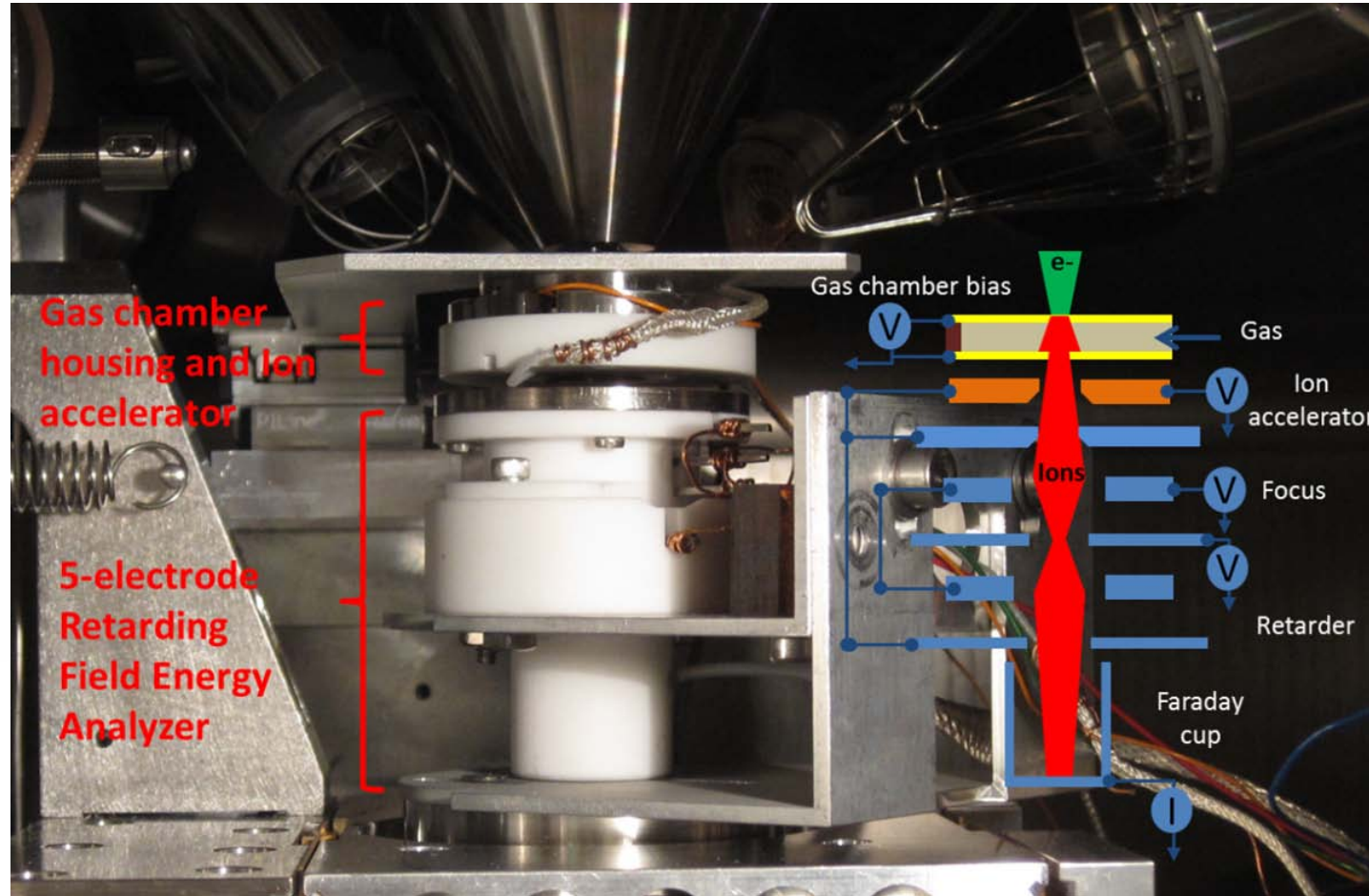
average ion residential time: 111 ps

total emission current: 1nA



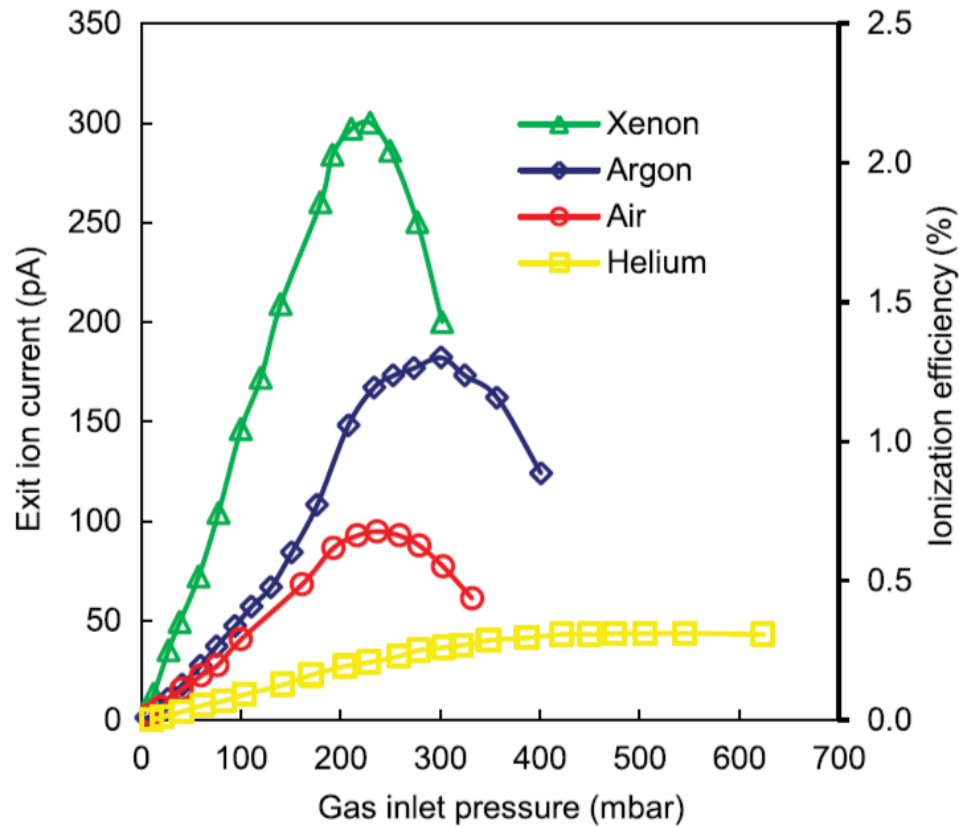
average ion interval = 160 ps

typically only one ion in the source at a time!



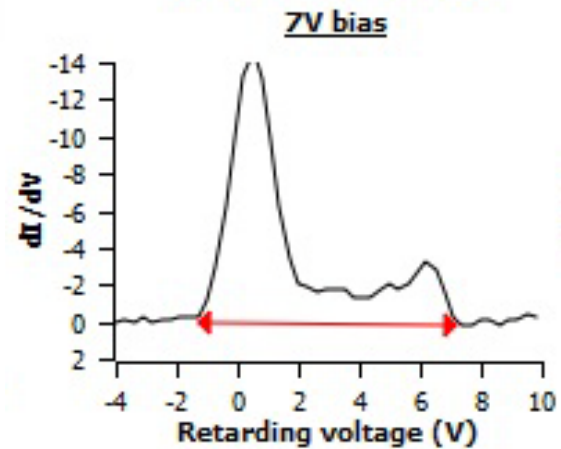
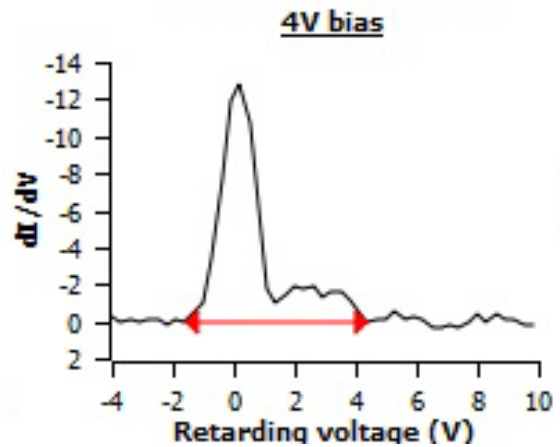
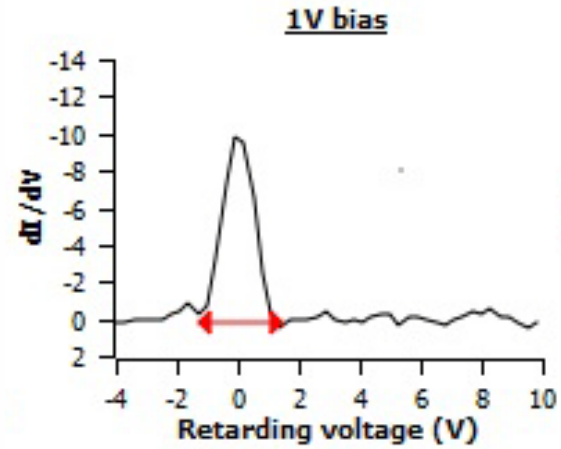
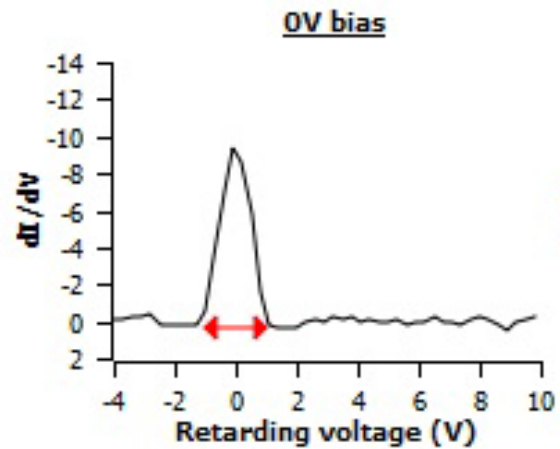


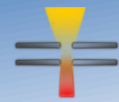
electron current: 14nA
membrane spacing: 2.3um
aperture diameter: 1.5 um





energy spread measurements





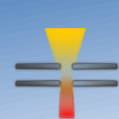
$$B_r = \frac{e}{4\pi} \frac{\sigma_I}{\sigma_C} \frac{J_e}{kT}$$

Cooling down the gas chamber:

- Brightness improved
- Energy spread unaffected ($kT \ll eV_b$)

Cooling with liquid helium or nitrogen: same device

Cooling by LASERs: alternative design



Conclusions

- Source for HR FIB systems: the **Nano aperture ion source**
- First tests inspiring

Outlook

- Replace Ga on a FEI DualBeam
- Measure brightness
- Explore applications
- Optimize by improved physical model
- Cool down ?

